

INFORMATION DISCLOSURE STATEMENT

Applicant	: Janne Kesala
App. No.	: Unknown
Filed	: Herewith
For	: METHOD AND APPARATUS FOR FEEDING GAS PHASE REACTANT INTO A REACTION CHAMBER
Examiner	: Unknown
Group Art Unit	: Unknown

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed is form PTO-1449 listing 8 references that are of record in U.S. patent application No. 09/854,706, filed May 14, 2001, which is the parent of this Continuation application, and is relied upon for an earlier filing date under 35 U.S.C. § 120. Copies of the references are not submitted pursuant to 37 C.F.R. § 1.98(d).

This Information Disclosure Statement is being filed before the receipt of a first Office Action on the merits, and presumably no fee is required in accordance with 37 C.F.R. § 1.97(b)(3). If a first Office Action on the merits was mailed before the mailing date of this Statement, the Commissioner is authorized to charge the fee set forth in 37 C.F.R. § 1.17(p) to Deposit Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: _____

10-28-03

By: _____



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FORM PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. SEPP14.001C1	APPLICATION NO. Unknown
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (USE SEVERAL SHEETS IF NECESSARY)		APPLICANT Janne Kesala	
		FILING DATE Herewith	GROUP Unknown

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
	1	4,058,430	11/15/77	Suntola et al.			
	2	4,389,973	06/1983	Suntola et al.			
	3	5,855,680	01/05/99	Soininen et al.			

FOREIGN PATENT DOCUMENTS								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	4	WO 01/36702 A1	05/25/01	PCT				

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)						
	5	M. Leskela et al., "Synthesis of oxide thin films and overlayers by atomic layer epitaxy for advanced applications," Materials Science & Engineering, Vol. B41 (1996), pages 23-29.					
	6	Niinisto et al., "ALD precursor chemistry: evolution and future challenges,": Journal de Physique IV. Vol. 9 (1999), pages Pr8-837-Pr8-852.					
	7	Pierson, Handbook of Chemical Vapor Deposition, (1992), pp.87-88.					
	8	Tuomo Suntola. "Atomic Layer Epitaxy," Thin Solid Films, Vol 216 (1992), pages 84-89.					

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EXAMINER	DATE CONSIDERED
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	